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(12)(KR)
(B1)(51) 。 Int. Cl.⁶
H01L 21/31(45)
(11)
(24)2004 04 13
10-0415338
2004 01 05(21) 10-1996-0047594
(22) 1996 10 23(65)
(43)10-1997-0023839
1997 05 30

(30) 08/547,074 1995 10 23 (US)

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(54)

(氣密)

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4
5
6
7
8
9
10

가

1

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가

2

(sacrificial material)

3

4

5

가

6

가

7

8

9

가 가 , 2

5,324,683

가 가 2

가 가

가 2

1 2 (' ') 1 (1) (2)

/

(: , , ,) , , ,

(sputtering) (PVD)

1 (3) 가 (4) 가 (4) 3 (6) (7) (3)

가 , 2 (5)

(6)

(PECVD), (ECR) (CVD), (focusing)

가 가 . 100 1,000

PECVD 가 (plasma field) CVD , 50 600 , (0.1 5watts/cm²) (10kHz 10⁻² MHz) (0.1 10GHz) 가) (: , (2) 5,011,706 (3) 가 , (ablation) (,), (,) / 5 (9) 4 (8) (9) 4,756,977 가 가 / 가 (9) 6 (11) (6) 7 (10) (10) 가 (12) 2 (2) (10) 8 (13) 가 (14) /

10

(氣密)

가

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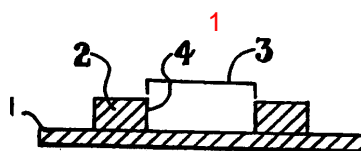
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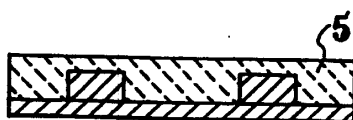
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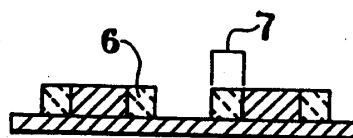
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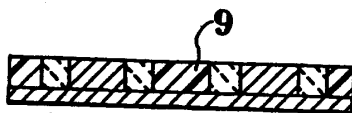
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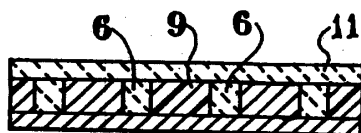
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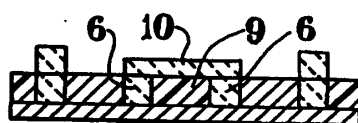
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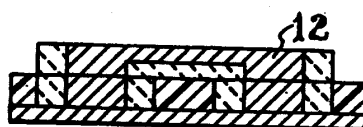
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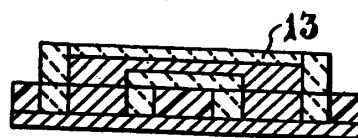
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